## Listing of Claims:

1. (Currently Amended) A method for manufacturing a diamond film comprising: forming a plasma of finite volume near a substrate by subjecting a gas containing at least hydrogen and carbon in a vacuum chamber to periodic pulsed discharges using a pulsed microwave plasma by applying a repeated succession of a low-power state and a high-power state, in which the ratio of the duration of the high-power state to the duration of the low-power state is between 1/9 and 1, and having a peak absorbed power Pc, so as to obtain at least carbon-containing radicals in the plasma, and depositing the said carbon-containing radicals on the substrate in order to form a diamond film thereon:

wherein the power being injected into the volume of the plasma with a peak power density of at least 100 W/cm³ while maintaining the substrate to a substrate temperature of between 700 °C and 1000 °C.

- (Currently amended) The method according to Claim 1, in which a plasma having at least one of the following features is generated near the substrate:
- the pulsed discharge has a certain peak absorbed power Pc-and the peak power density to the volume of the plasma is between 100 W/cm³ and 250 W/cm³,
  - the maximum temperature of the plasma is between 3500 K and 5000 K.
- the temperature of the plasma in a boundary region of the plasma located less than 1 cm from the surface of the substrate is between 1500 K and 3000 K and
- the plasma contains hydrogen atoms having a maximum concentration in the plasma of between  $1.7 \times 10^{16}$  and  $5 \times 10^{17}$  cm<sup>-3</sup>.
- (Previously Presented) The method according to Claim 1 or Claim 2, in which said gas contains carbon and hydrogen in a carbon/hydrogen molar ratio of between 1% and 12%.
- 4. (Previously Presented) The method according to Claim 1, in which said gas contains at least one hydro-carbon, and a plasma having a concentration of the carbon-containing radicals of between 2×10<sup>14</sup> cm<sup>-3</sup> and 1×10<sup>15</sup> cm<sup>-3</sup> is generated.
- (Cancelled)

- (Previously Presented) The method according to Claim 1, in which at least one of the following parameters is estimated:
  - a substrate temperature,
  - a temperature of the plasma,
- a temperature of the plasma in said boundary region, located less than 1 cm from the surface of the substrate.
  - a concentration of atomic hydrogen in the plasma,
  - a concentration of carbon-containing radicals in the plasma,
- a concentration of carbon-containing radicals in said boundary region close to the plasma.
  - a pressure of the plasma and
  - a power density of the plasma,

and the power emitted as a function of time is adapted according to at least one of these parameters.

- (Currently amended) The method according to Claim 1, in which the plasma is contained
  in a cavity with at least one of the following properties:
- the <u>periodic pulsed discharges pulsed discharge has have</u> a peak power of at least 5 kW at 2.45 GHz,
  - the pressure of the plasma is between 100 mbar and 350 mbar and
- the gas containing hydrogen and carbon is emitted with a ration of the flow rate to the volume of plasma of between 0.75 and 7.5 sccm/cm³.
- 8. (Currently amended) The method according to Claim 1, in which the plasma is contained in a cavity with at least one of the following properties:
- the <u>periodic pulsed discharges have pulsed discharge has</u> a peak power of at least 10 kW at 915 MHz.
  - the pressure of the plasma is between 100 mbar and 350 mbar and
  - the gas containing hydrogen and carbon is emitted with a ratio of the flow rate to the volume of the plasma of between 0.75 and 7.5 sccm/cm³.